

Form PTO-1449

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

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 APPLICATION NO.
NEW

 APPLICANT
Sungho JIN et al.

 FILING DATE
June 23, 1999

 GROUP
Unassigned

 10511 U.S. PTO
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U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER							DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
TS	5	4	2	6	6	8	6	1995-06-20	Rentzepis et al.			

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER							DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION	
												YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

TS	W. DeVore et al., "High emittance electron gun for projection lithography", 1998 American Vacuum Society, J. Vac. Sci. Technol. B14(6), Nov./Dec., 1996, pp. 3764-3769
TS	W.K. Waskiewicz et al., "Design of a Low-Brightness, Highly Uniform Source for Projection Electron-Beam Lithography (SCALPEL)", Proc. SPIE, 3155, 1997
TS	J. Hasker et al., "Cathode and Scaling Properties Related to the Shape of Current-Voltage Characteristics", Applied Surface Science 24 (1985), pp. 318-329
TS	Robert Bakish, "Introduction to Electron Beam Technology", pp. 73-74

EXAMINER Shelma Sheree Clove	DATE CONSIDERED 7-31-01
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

RCS:JAC:mdp